

## Supplementary Information

# **Electronic-Reconstruction-Enhanced Hydrogen Evolution Catalysis in Oxide Polymorphs**

*Li et al.*

### **This document includes:**

Supplementary Figures;

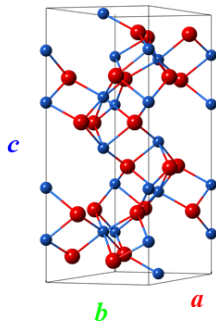
Supplementary Tables;

Supplementary Notes;

Supplementary References;

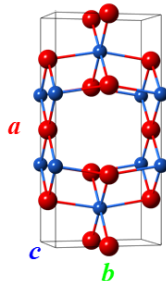
## Supplementary Figures

**a**  $\alpha$ -Ti<sub>2</sub>O<sub>3</sub> (Trigonal)



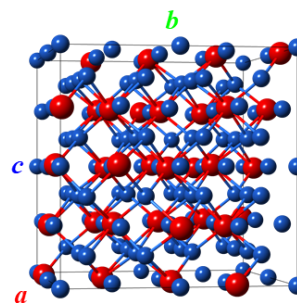
$$\begin{aligned} a &= b = 5.15 \text{ \AA} \\ c &= 13.61 \text{ \AA} \\ \alpha &= \beta = 90^\circ, \gamma = 120^\circ \end{aligned}$$

**b**  $o$ -Ti<sub>2</sub>O<sub>3</sub> (Orthorhombic)



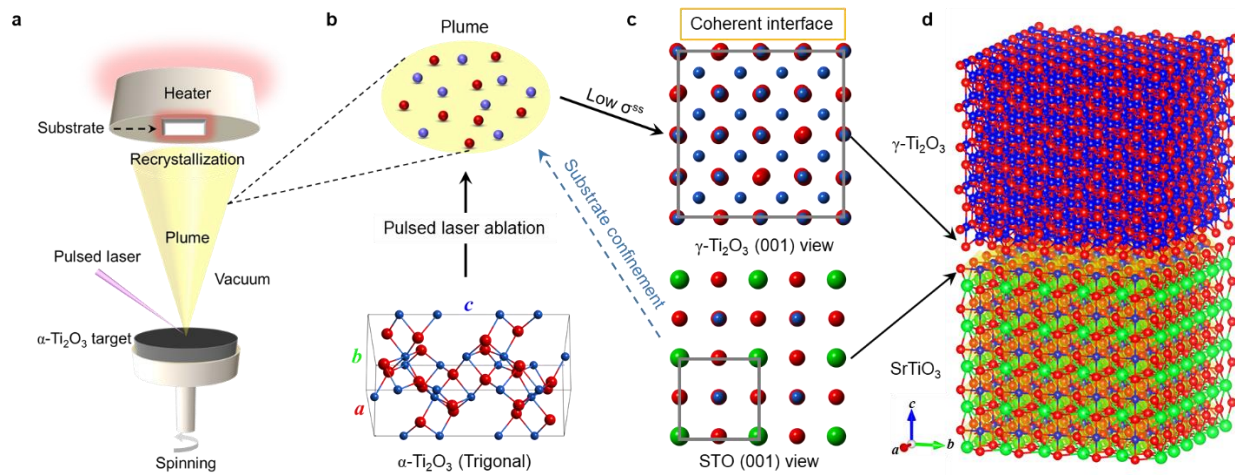
$$\begin{aligned} a &= 9.385 \text{ \AA}, b = 4.4225 \text{ \AA}, \\ c &= 2.8095 \text{ \AA} \\ \alpha &= \beta = \gamma = 90^\circ \end{aligned}$$

**c**  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> (Cubic)

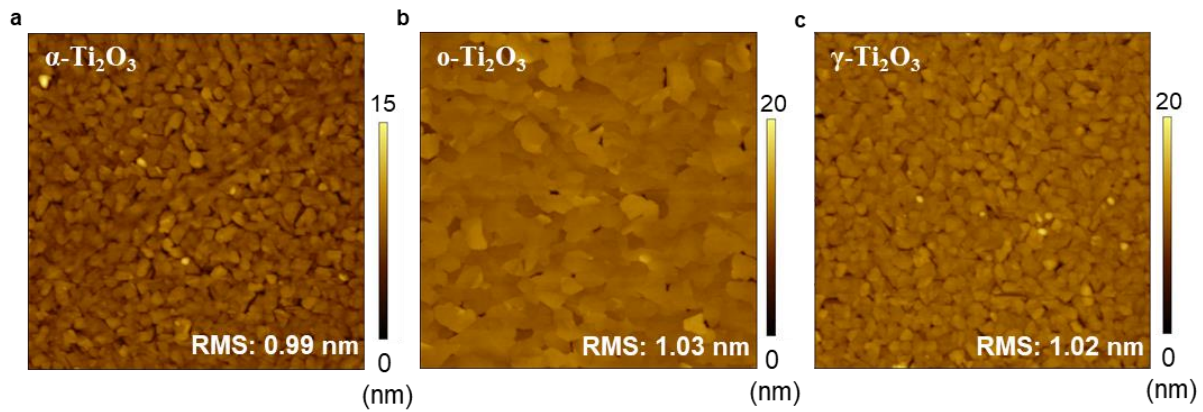


$$\begin{aligned} a &= b = c = 8.48 \text{ \AA} \\ \alpha &= \beta = \gamma = 90^\circ \end{aligned}$$

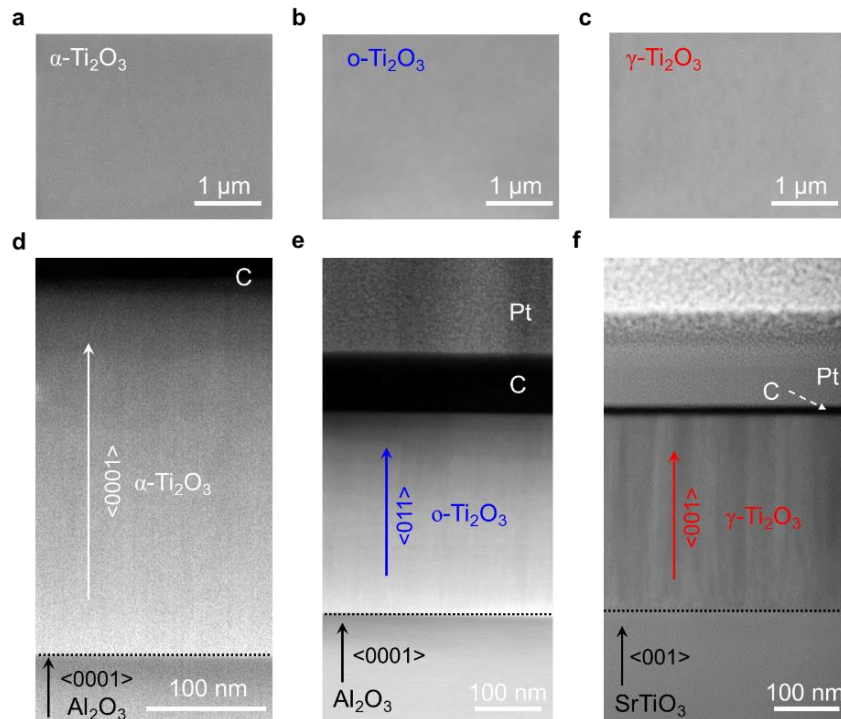
**Supplementary Figure 1 | Lattice parameters for Ti<sub>2</sub>O<sub>3</sub> polymorphs. a,  $\alpha$ -Ti<sub>2</sub>O<sub>3</sub>, b,  $o$ -Ti<sub>2</sub>O<sub>3</sub>, c,  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub>.**



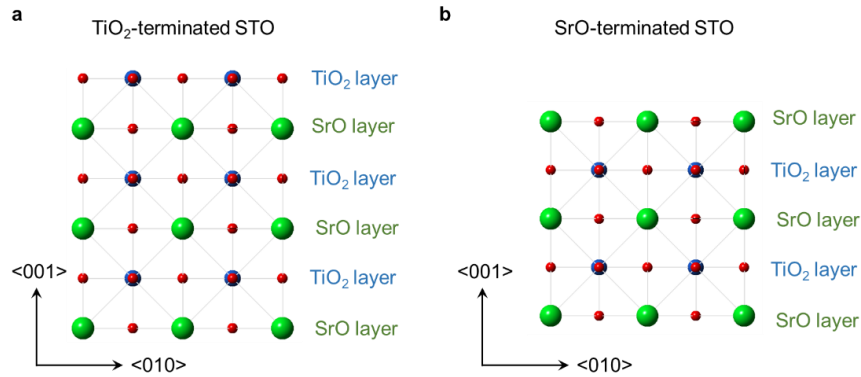
**Supplementary Figure 2 | Schematic of the epitaxial stabilization of  $\gamma\text{-Ti}_2\text{O}_3$ .** **a** PLD process. **b** Plume formation by pulsed laser ablation. **c** Cubic/cubic coherent interface with low  $\sigma^{ss}$  formed between  $\gamma\text{-Ti}_2\text{O}_3$  and STO due to the confinement of the substrate. **d** Epitaxial stabilization of the  $\gamma\text{-Ti}_2\text{O}_3$  based on the cubic/cubic coherent interface.



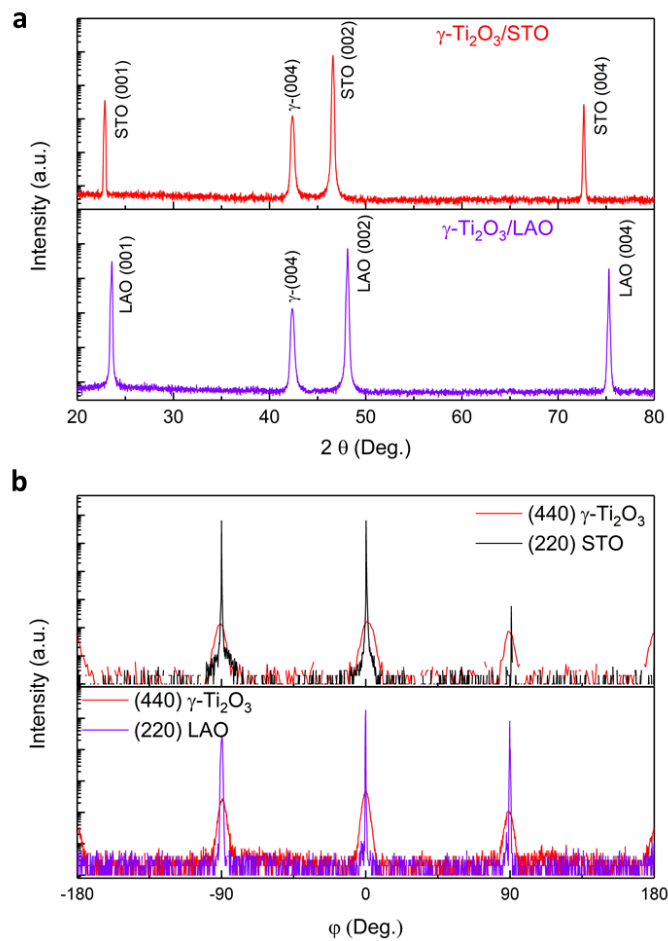
**Supplementary Figure 3 | Surfaces of the  $\text{Ti}_2\text{O}_3$  films.** a-c AFM images of the  $\alpha\text{-Ti}_2\text{O}_3$ ,  $o\text{-Ti}_2\text{O}_3$ , and  $\gamma\text{-Ti}_2\text{O}_3$  films, respectively. The image size is  $2 \times 2 \mu\text{m}$ .



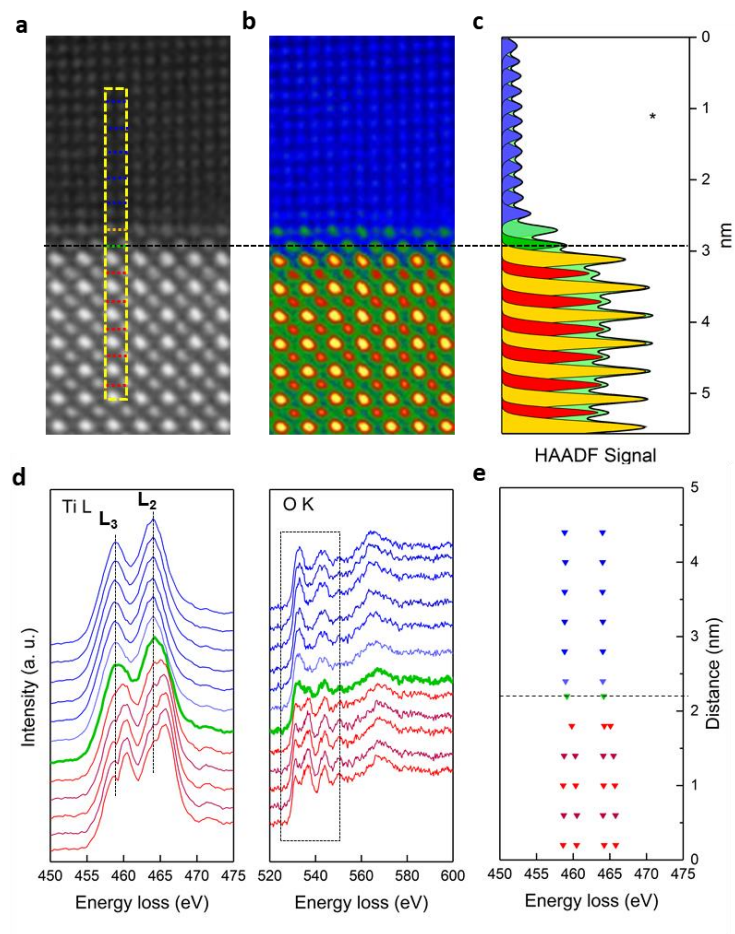
**Supplementary Figure 4 | Surfaces and cross-sections of the Ti<sub>2</sub>O<sub>3</sub> films characterized by electron microscopes.** a-c SEM images collected from the surfaces of α-Ti<sub>2</sub>O<sub>3</sub>, o-Ti<sub>2</sub>O<sub>3</sub>, and γ-Ti<sub>2</sub>O<sub>3</sub> films, respectively. d-f Low-resolution STEM images collected from the cross-sections of α-Ti<sub>2</sub>O<sub>3</sub>, o-Ti<sub>2</sub>O<sub>3</sub>, and γ-Ti<sub>2</sub>O<sub>3</sub> films, respectively.



**Supplementary Figure 5 | STO surfaces with different terminations.** **a** and **b** are schematic presentations of  $\text{TiO}_2$ -terminated and SrO-terminated STO, respectively. Along with the  $\langle 001 \rangle$  direction, STO is made by alternative SrO layers and  $\text{TiO}_2$  layers. Thus, the surface of STO substrates could be the  $\text{TiO}_2$  layer-terminated or the SrO layer-terminated. Since the STO substrates used in our experiments were all etched by hydrofluoric acid and then annealed at  $950^\circ\text{C}$  for 3 hours, the SrO layer would be removed. Then, the surface of the STO substrate is  $\text{TiO}_2$  layer terminated. The process we used to deal with the STO substrates is a well-known and commonly utilized method to obtain the  $\text{TiO}_2$  layer terminated STO substrates<sup>1</sup>.  $\text{TiO}_2$ -STO refers to “ $\text{TiO}_2$  layer terminated STO”.

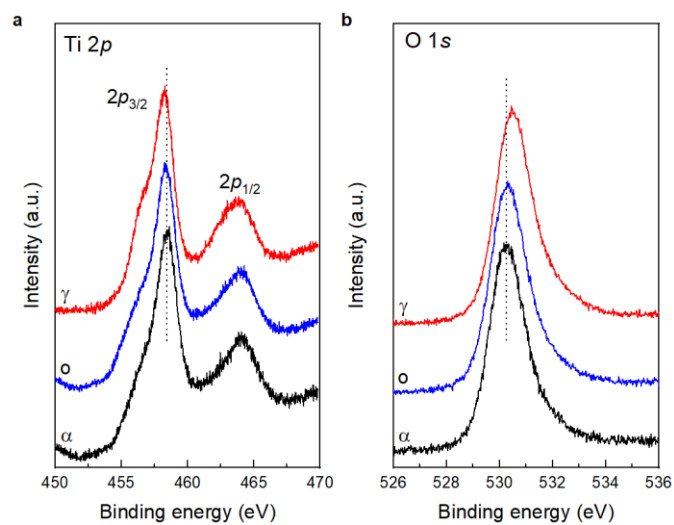


**Supplementary Figure 6 | Crystal structural characterization of  $\gamma\text{-Ti}_2\text{O}_3$  by XRD. a**, HR-XRD patterns for  $\gamma\text{-Ti}_2\text{O}_3/\text{STO}$  and  $\gamma\text{-Ti}_2\text{O}_3/\text{LAO}$  heterostructures. **b**, Synchrotron-based in-plane  $\phi$ -scans for  $\gamma\text{-Ti}_2\text{O}_3/\text{STO}$  and  $\gamma\text{-Ti}_2\text{O}_3/\text{LAO}$  heterostructures. Source data are provided as a Source Data file.

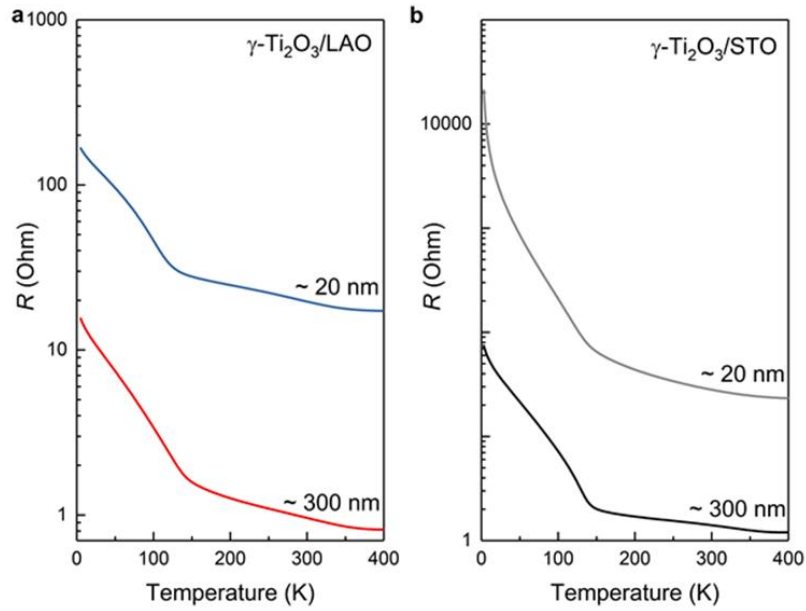


**Supplementary Figure 7 | Microstructural characterizations of  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> by HR-STEM and EELS. a** and **b** are HAADF-STEM images for the  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub>/STO interface, shown in the grayscale and temperature scale, respectively. The black dashed line presents the position of the TiO<sub>2</sub>-terminated layer. **c**, HAADF signal profile obtained from **a**. **d**, EELS spectra of Ti L<sub>2,3</sub> and O K-edges obtained from the line scan across the interface shown in **a**. **e**, Peak positions of the Ti L<sub>2,3</sub> edge, deduced from **d**.

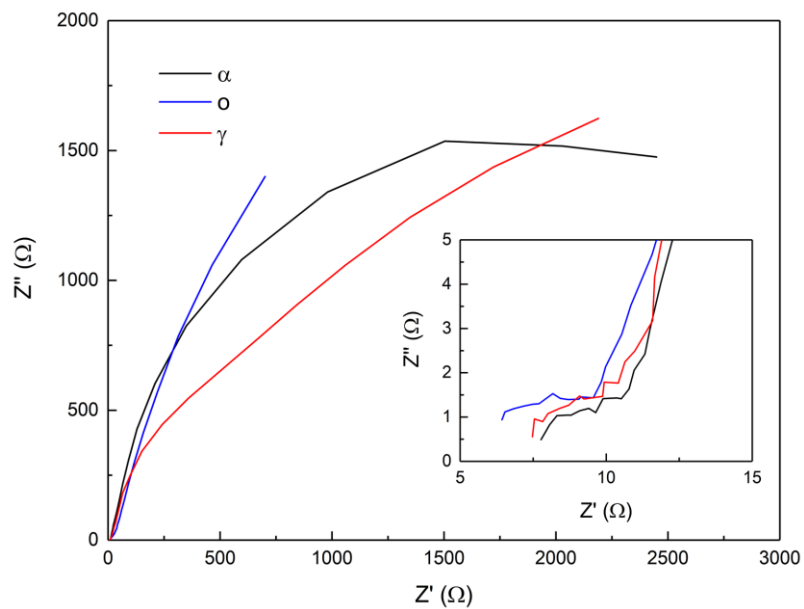




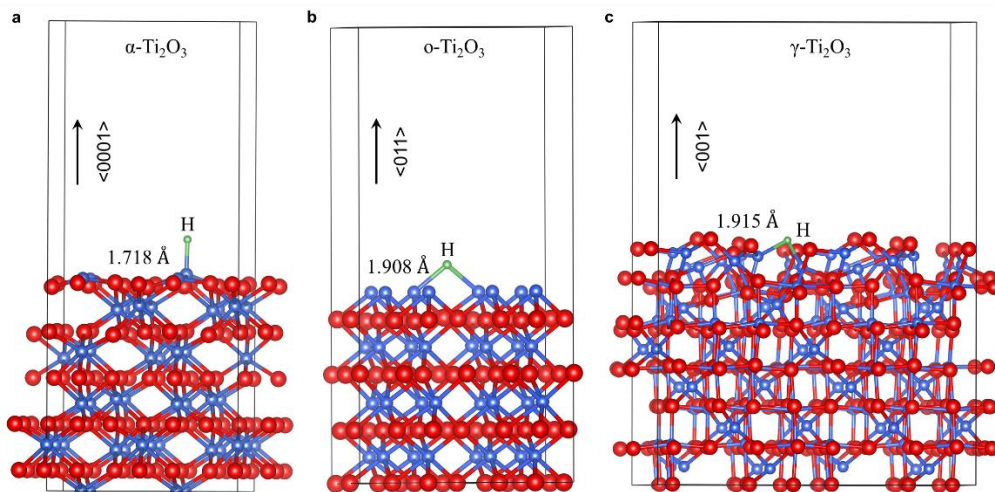
**Supplementary Figure 8 | XPS. a** Ti  $2p$  and **b** O  $1s$  XPS spectra collected from  $Ti_2O_3$  polymorphs. Source data are provided as a Source Data file.



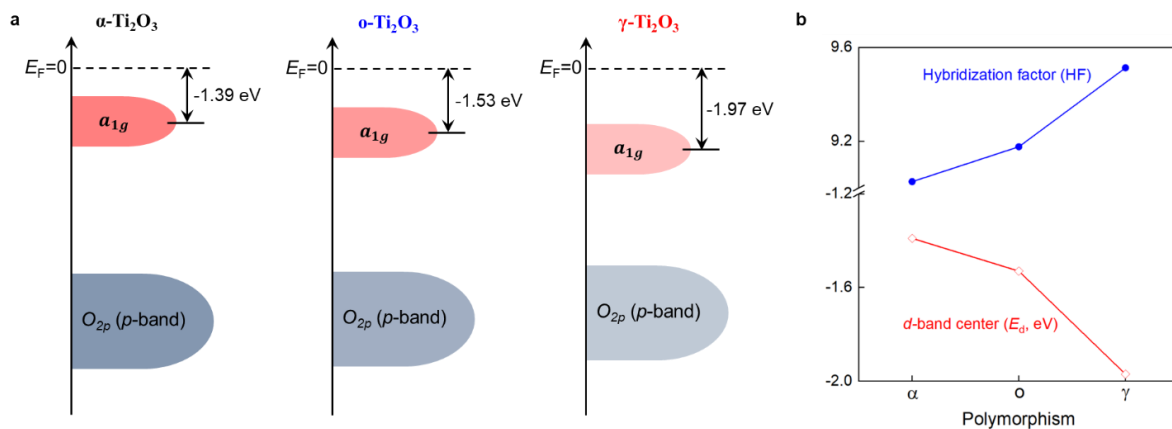
**Supplementary Figure 9 | Thickness- and substrate-dependence of the electrical property of  $\gamma\text{-Ti}_2\text{O}_3$ .** Temperature-dependent resistance of  $\gamma\text{-Ti}_2\text{O}_3$  films with different thickness on **a** LAO and **b** STO substrates, respectively. Source data are provided as a Source Data file.



**Supplementary Figure 10 | Electrochemical impedance spectroscopy.** The impedance data for the  $\text{Ti}_2\text{O}_3$  polymorphs is collected in 0.5 M  $\text{H}_2\text{SO}_4$  and before the HER measurements. Source data are provided as a Source Data file.



**Supplementary Figure 11 | Optimized models of H adsorbed on the surfaces of  $\text{Ti}_2\text{O}_3$  polymorphs. **a**  $\alpha\text{-Ti}_2\text{O}_3$  (0001) surface. **b**  $\text{o-Ti}_2\text{O}_3$  (011) surface. **c**  $\gamma\text{-Ti}_2\text{O}_3$  (001) surface. The red, blue and green spheres represent oxygen, titanium and hydrogen atoms, respectively.**



**Supplementary Figure 12 | Theoretical calculation of the  $d$ -band center for  $\text{Ti}_2\text{O}_3$  polymorphs. a** Schematic presentation of the  $d$ -band center for different  $\text{Ti}_2\text{O}_3$  polymorphs. **b** Correlation between the Ti-O hybridization and  $d$ -band center. Source data are provided as a Source Data file.

## Supplementary Tables

Polymorphism	Ti 2 <i>p</i> <sub>3/2</sub> (eV)	Ti 2 <i>p</i> <sub>1/2</sub> (eV)	O 1 <i>s</i> (eV)
$\alpha$ -Ti <sub>2</sub> O <sub>3</sub>	458.41	464.06	530.26
$\alpha$ -Ti <sub>2</sub> O <sub>3</sub>	458.35	463.95	530.30
$\gamma$ -Ti <sub>2</sub> O <sub>3</sub>	458.20	463.73	530.48

Supplementary Table 1 | The peak positions of XPS spectra in [Supplementary Figure 8](#).

## Supplementary Note 1

It should be noted that the trigonal  $\alpha$ -Ti<sub>2</sub>O<sub>3</sub> is the thermodynamic stable phase of Ti<sub>2</sub>O<sub>3</sub> and exists in bulk nature, while the cubic  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> and orthorhombic o-Ti<sub>2</sub>O<sub>3</sub> are metastable phases that have not been fabricated in the bulk-form. High-pressure high temperature measurements are usually used to study the polymorphism of materials, while the polymorphic transitions could be detected by XRD or Raman<sup>2-5</sup>. For Ti<sub>2</sub>O<sub>3</sub>, only one golden orthorhombic phase was fabricated at high temperatures and high pressures<sup>4,6</sup>. Thus, the formation energy of  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> and o-Ti<sub>2</sub>O<sub>3</sub> should be higher than that of the golden phase or much more energy is needed for the polymorphic transitions.

However, the epitaxial growth of oxides in the film form on the single crystal substrates is a different scenario. Pulsed laser deposition (PLD) technique was used to fabricate the Ti<sub>2</sub>O<sub>3</sub> polymorphs in this work. As shown in [Supplementary Figure 2a](#), an ultraviolet (UV: 248 nm) pulsed laser beam (pulse duration, 10-50 ns) is focused with a high energy density of  $\sim 2$  J/cm<sup>2</sup> onto the spinning  $\alpha$ -Ti<sub>2</sub>O<sub>3</sub> target. The laser pulse is absorbed by the target, and the energy of the laser is converted to thermal energy. Rapid heating and vaporization of the target material occur at the focusing area, generating an expanding plasma plume which contains atoms, molecules, and ions, in both ground and excited states, as well as energetic electrons<sup>7</sup>. The atoms and ions undergo collisions in the high-density region near the target to create a highly directional expansion perpendicular to the target surface with initial velocities above  $10^6$  cm/s, then propagates with gradually decreased velocity to the heated substrates (6 cm away from the target). The atoms and ions will nucleate, and then grow into the epitaxial films with different orientations or phases on the surface of the substrates, depending on the nature (orientation, structure, and symmetry) of the substrates and its temperature<sup>7</sup>. Thus, a recrystallization process occurs on the surface of the substrates during growth. Moreover, with tunable kinetic energy of the atoms and ions inside of the plume via controlling the laser energy, the  $P$ - $T$  phase diagram of the target material is changed during the film deposition process on the substrate's surface, making it possible to fabricate new bulk-absent metastable phases in the film form with the confinement of substrates<sup>30</sup>.

During the epitaxial growth, the single crystalline substrates act as the seed crystal, the deposited film will lock into the same in-plane symmetry and crystallographic orientation with respect to the substrate crystal, forming the coherent or semicoherent film/substrate interface<sup>30</sup>. Since the energy of the coherent and semicoherent interfaces is significantly lower than that of the

noncoherent ones<sup>8</sup>, the interfaces formed can affect the choice of the nucleus (film) crystallographic structure because the system tends to minimize the free energy to reach the equilibrium state. Thus, we can control the orientation of the films using different orientated single crystalline substrates<sup>9</sup>, and we can also control the crystallographic structure of the film via changing the in-plane symmetry of the substrates' surface<sup>31</sup>.

Thus, the crystallographic structure realized in the epitaxial films can be different from that of the equilibrium bulk material, which is called "epitaxial stabilization"<sup>30,10</sup>. From the thermodynamic point of view, epitaxial stabilization demands the change of equilibrium phase due to the epitaxial growth. In particular, the change of the pressure ( $P$ )-temperature ( $T$ ) diagrams is realized for the epitaxial stabilization of metastable polymorphs<sup>30</sup>. We need to point out that most of the metastable phases epitaxially stabilized in the film-form could be found in the  $P$ - $T$  phase diagram, which is the usual cases. However, there are few unusual cases that is some bulk-absent phases can only be epitaxially stabilized on the substrates in the film-form, such as body-centered cubic (bcc) Co<sup>11</sup>, hexagonal TbMnO<sub>3</sub><sup>31</sup>, and orthorhombic Ti<sub>2</sub>O<sub>3</sub> ( $Immm$ )<sup>28</sup>. This is because the pressure-temperature induced polymorphic transition is a thermodynamic equilibrium process between different structures, while the epitaxial growth is a non-equilibrium process with the confinement of the substrates. The epitaxial stabilization of the metastable phases in the film-form is a more complicated process than the bulk phase transitions. However, it is a very fascinating method to study the emergent properties of the epitaxially stabilized metastable phases.

In this work, the trigonal  $\alpha$ -Ti<sub>2</sub>O<sub>3</sub> was grown on trigonal  $\alpha$ -Al<sub>2</sub>O<sub>3</sub> single crystalline substrates with the same (trigonal) in-plane symmetry (Figure 1e), forming the coherent film/substrate interface. For the stabilization of cubic  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub>, we change the substrate from trigonal Al<sub>2</sub>O<sub>3</sub> to cubic SrTiO<sub>3</sub> (STO). As shown in Supplementary Figure 2a, a plume will be generated when the pulsed laser is focused on the target ( $\alpha$ -Ti<sub>2</sub>O<sub>3</sub>). Meanwhile, the crystal structure of the  $\alpha$ -Ti<sub>2</sub>O<sub>3</sub> is broken, forming the titanium and oxygen atoms or ions (Supplementary Figure 2b) inside of the plasma plume. When the atoms or ions arrived at the surface of the heated substrates (STO), the in-plane symmetry of the substrate will provide a confinement effect to drive the atoms or ions to form the (cubic  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub>/cubic STO) coherent interface (Supplementary Figure 2c) on the substrate (cubic STO), minimizing the solid-solid interface energy ( $\sigma^{ss}$ ). Based on this cubic/cubic coherent interface, the cubic  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> is epitaxially stabilized on the cubic STO substrate (Supplementary Figure 2d).



As for the stabilization of the o-Ti<sub>2</sub>O<sub>3</sub>, even though the in-plane symmetry for (011) o-Ti<sub>2</sub>O<sub>3</sub> and (0001) Al<sub>2</sub>O<sub>3</sub> is orthorhombic and trigonal from one unit cell view (Figure 1d), which seems like a noncoherent interface. However, if we extend the unit cells, we can find a semicoherent interface between the (011) o-Ti<sub>2</sub>O<sub>3</sub> and (0001) Al<sub>2</sub>O<sub>3</sub>. It is well known that the trigonal Al<sub>2</sub>O<sub>3</sub> also has the hexagonal symmetry if we extend its Z number from 2 to 6. For (011) o-Ti<sub>2</sub>O<sub>3</sub>, the in-plane symmetry is slightly “distorted hexagonal” from the multi-unit cells view<sup>29</sup>. As a result, a “semicoherent” interface was formed between the (011) o-Ti<sub>2</sub>O<sub>3</sub> and (0001) Al<sub>2</sub>O<sub>3</sub>. Thus, the orthorhombic o-Ti<sub>2</sub>O<sub>3</sub> was stabilized and fabricated on the Al<sub>2</sub>O<sub>3</sub> substrates in the film form. We need to point out that the deposition temperature for α-Ti<sub>2</sub>O<sub>3</sub> and γ-Ti<sub>2</sub>O<sub>3</sub> is 600 °C, while that for o-Ti<sub>2</sub>O<sub>3</sub> is 900 °C, indicating a little bit higher energy is needed to form this “semicoherent” interface.

## Supplementary Note 2

In order to determine the cubic  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub>, HR-XRD and synchrotron-based in-plane  $\phi$ -scans were performed. As shown in [Supplementary Figure 6a](#), in addition to the (00 $l$ ) peaks from the STO and LAO substrates, only (004) peak of the  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> was observed without any impurity phase, which was consistent with that of the  $\gamma$ -Al<sub>2</sub>O<sub>3</sub>/STO heterostructure<sup>40</sup>. As expected, fourfold symmetry was also observed in the in-plane  $\phi$ -scans ([Supplementary Figure 6b](#)) for the (440)  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> and (220) STO or LAO, confirming the cubic-on-cubic epitaxial growth of  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> on STO or LAO. As a consequence, the epitaxial relationship between  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> film and STO substrate was confirmed to be (004)  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub>//(002) STO and  $\langle 100 \rangle$   $\gamma$ -Ti<sub>2</sub>O<sub>3</sub>// $\langle 100 \rangle$  STO. The same scenario was shared with the  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub>/LAO.

### Supplementary Note 3

High resolution STEM and EELS were used to study the  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub>/STO interface. Clean and shape interface was observed in [Supplementary Figure 7a-c](#), demonstrating the good epitaxy between  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> and STO. As mentioned in the man text, the epitaxial relationship was confirmed to be  $\langle 100 \rangle \gamma$ -Ti<sub>2</sub>O<sub>3</sub>// $\langle 100 \rangle$  STO and  $\langle 001 \rangle \gamma$ -Ti<sub>2</sub>O<sub>3</sub>// $\langle 001 \rangle$  STO, which was consistent with the XRD results. Furthermore, EELS line scan was performed to investigate the valence evolution of Titanium across the interface. As shown in [Supplementary Figure 7d](#) and [e](#), four-peak feature was changed to two-peak feature across the interface, indicating the valence state of Ti was changed from 4+ to 3+<sup>43</sup>. Simultaneously, EELS spectra at the O *K*-edge was also varied with the evolution of Ti states, demonstrating the Ti-O hybridization was changed from STO to  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub>. By now, Ti<sup>3+</sup> was confirmed in the newly stabilized  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> polymorph via both XAS ([Fig. 4a](#)) and EELS from the surface and interface, respectively. Combined with the XRD and STEM results, the new  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub>, as an isomorph of  $\gamma$ -Al<sub>2</sub>O<sub>3</sub> and  $\gamma$ -Fe<sub>2</sub>O<sub>3</sub>, was determined to stabilized on STO and LAO substrates.

## Supplementary Note 4

X-ray photoelectron spectroscopy (XPS) was also performed to characterize the electronic structure and Ti-O hybridization on the  $\text{Ti}_2\text{O}_3$  films' surfaces. As shown in [Supplementary Figure 8](#) and [Supplementary Table 1](#), compared to that of  $\alpha\text{-Ti}_2\text{O}_3$ , the Ti  $2p_{3/2}$  and  $2p_{1/2}$  main peaks for  $\alpha\text{-Ti}_2\text{O}_3$  and  $\gamma\text{-Ti}_2\text{O}_3$  are slightly shifted to lower binding energy, while the O  $1s$  peaks are slightly shifted to higher binding energy. The binding energy of the Ti  $2p_{3/2}$  main peak in  $\gamma\text{-Ti}_2\text{O}_3$  is the lowest, demonstrating the strongest Ti  $3d$  - O  $2p$  hybridization<sup>59</sup>, consistent with the XAS results.

## Supplementary Note 5

Since the resistivity of the semiconductor can be shown as:  $\rho = \frac{1}{q n \mu}$ ; where  $q$  is the elementary charge ( $1.602 \times 10^{-19}$  coulombs),  $n$  and  $\mu$  are concentration and mobility of the majority carriers, respectively. Thus, the resistivity is inversely proportional to the carrier concentration and mobility. That is, the resistivity will increase with the carrier concentration and mobility decrease.

Specifically, in  $\alpha$ -Ti<sub>2</sub>O<sub>3</sub> (Figure 5), the carrier concentration is decreased with decreasing temperature, which will increase the resistivity. However, the mobility is increased at lower temperatures, which will decrease the resistivity. That is, the changes of the carrier concentration and mobility with the reduced temperature have an opposite impact on its resistivity. Thus, the resistivity of  $\alpha$ -Ti<sub>2</sub>O<sub>3</sub> is increased at low temperatures as a result of the destructive effect between the carrier concentration and mobility. Similarly, in  $\sigma$ -Ti<sub>2</sub>O<sub>3</sub> (Figure 5), the carrier mobility is decreased with decreasing temperature, while the carrier concentration is anomaly increased at lower temperatures ( $T < 250$  K). Hence, the increase of the resistivity of  $\sigma$ -Ti<sub>2</sub>O<sub>3</sub> is also a result of the destructive effect between the carrier concentration and mobility.

However, in  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> (Figure 5), both the carrier concentration and mobility are decreased with the temperature decrease, and they have the same impact on the resistivity, that is, they will both make the resistivity increase. So, the increase of the resistivity of  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub> is a result of the constructive effect between the carrier concentration and mobility, which results in the larger change of resistivity in  $\gamma$ -Ti<sub>2</sub>O<sub>3</sub>.

## Supplementary Note 6

It should be noted that all the  $\text{Ti}_2\text{O}_3$  samples were fabricated by the PLD technique (Supplementary Figure 2a), resulting in the dense, flat, and fully covered film/substrates heterostructures. As shown in Supplementary Figure 3, the surfaces of the films are very flat (RMS:  $\sim 1$  nm). Thus, there would not be a big difference in the surface area (or specific surface area) of the  $\text{Ti}_2\text{O}_3$  film samples.

As for the defects, in our previous work<sup>28</sup>, those samples were deposited in very high vacuum ( $\sim 3.0 \times 10^{-9}$  Torr) in order to create some oxygen vacancies in the samples. In this work, we reduced the vacuum to around  $3.0 \times 10^{-6}$  Torr to suppress the formation of oxygen vacancies. Since the  $\text{Ti}_2\text{O}_3$  films were deposited at high temperatures (above 600 °C), they could be oxidized to  $\text{TiO}_2$  with a small amount of  $\text{O}_2$  at the  $\text{O}_2$  partial pressure of  $5.0 \times 10^{-4}$  Torr<sup>28</sup>. Depending on these experience,  $3.0 \times 10^{-6}$  Torr was confirmed to be an optimized vacuum condition to get pure-phase of  $\text{Ti}_2\text{O}_3$  films with minimized formation of oxygen vacancies. Since we kept the vacuum at the same value ( $\sim 3.0 \times 10^{-6}$  Torr) when we fabricated all the samples in this work, the oxygen vacancies in the  $\text{Ti}_2\text{O}_3$  polymorphs should be suppressed.

Synchrotron-based XAS was used to check the defects in the  $\text{Ti}_2\text{O}_3$  polymorphs. As shown in Figure 4a, the Ti  $L_3$ , and  $L_2$ -edge XAS spectra of all  $\text{Ti}_2\text{O}_3$  polymorphs are very similar, and located at  $\sim 458.6$  and  $\sim 463.7$  eV respectively, which are consistent with the bulk  $\text{Ti}_2\text{O}_3$  samples<sup>56</sup>, demonstrating the  $\text{Ti}^{3+}$  chemical environments in the  $\text{Ti}_2\text{O}_3$  polymorphs. X-ray photoelectron spectroscopy (XPS) was also performed to characterize the defects on films' surfaces (Supplementary Figure 8). As expected, the Ti  $2p$  and O  $1s$  spectra of the  $\text{Ti}_2\text{O}_3$  polymorphs are almost identical (with slight shifts, which results from their different Ti-O hybridization). The positions of the XPS peaks of Ti  $2p_{3/2}$  and  $2p_{1/2}$ , located around 458.4 and 464.0 eV respectively, are consistent with those of the  $\text{Ti}_2\text{O}_3$  bulk single crystals<sup>12</sup>, indicating the  $\text{Ti}^{3+}$  chemical environments in those  $\text{Ti}_2\text{O}_3$  polymorphs. By now, both XAS and XPS results confirm the  $\text{Ti}_2\text{O}_3$  polymorphs are sharing the same Ti valence state of  $3+$ , with minimized oxygen vacancies. Thus, with determinations of almost the same roughness (surface area) and Ti valence state in the  $\text{Ti}_2\text{O}_3$  polymorphs, we can rule out those possible effects which may contribute to the observed polymorph-dependent HER performance.

## Supplementary Note 7

Several diverse groups of materials including transition metal sulfides<sup>13,14</sup>, selenides<sup>15</sup>, and phosphides<sup>16,17</sup> have been exploited as efficient noble-metal-free HER catalysts with different benefits and drawbacks<sup>18-20</sup>. Recently, transition metal oxides are attracting more attention as an efficient HER catalyst<sup>2,23,21</sup> with compositional flexibility and environmental friendliness, whereas they were usually regarded as the HER inactive materials before, because of the unsuitable adsorption energy of H on the oxygen atoms. By now, the mechanism of the observed HER activity in oxides is still not clear. Thus, new mechanism of HER, based on the oxides' characteristics, e.g. metal-oxygen hybridization, needs to be explored for the oxide HER electrocatalysts.

Ti<sub>2</sub>O<sub>3</sub> shows excellent structural flexibility<sup>28</sup> and tunable electronic structures with relatively high and polymorph-dependent HER performances, which provides a wonderful platform to study the HER mechanism of oxides. By investigating the electronic structures and HER in different Ti<sub>2</sub>O<sub>3</sub> polymorphs via experimental and theoretical methods, strong correlation between the Ti-O hybridization and HER performance was established. Stronger hybridization of Ti 3*d* and O 2*p* orbitals lowered the *d*-band center of Ti, which weakens the H\* adsorption, resulting in the enhanced HER efficiency.

We believe this conclusion could be extended to other transition metal oxide systems. Thus, based on the investigation of Ti<sub>2</sub>O<sub>3</sub>, a new strategy is provided to further improve the HER performance of oxides by increase the metal-oxygen hybridization, which will help for exploring more efficient oxide HER catalysts. Besides, since the samples in this work are epitaxial films with flat surfaces ([Supplementary Figure 3](#)), which is quite different from those of the other groups of materials discussed above, the HER active area of the Ti<sub>2</sub>O<sub>3</sub> (flat films) is actually limited. Thus, we believe the HER activity of the Ti<sub>2</sub>O<sub>3</sub> (films) could be further enhanced by increasing the surface area via nanostructure-array fabrications.

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